

SPUTTERING TARGET

ABSTRACT

5 Provided is a sputtering target that comprises an Fe-Pt based alloy phase,
a Ag phase, and a C phase. In the composition of the entire sputtering target,
the value obtained by dividing the atomic number ratio of C by the atomic number
ratio of Ag is 4 to 10. In a cross section of the sputtering target, the Ag phase
10 has a shape that is included in every imaginary circle having a radius of 10 μm
drawn with its center at an arbitrary point in the Ag phase or a shape that has at
least two tangent points or intersection points between the imaginary circle and
the periphery of the Ag phase. It is an object of the present invention to provide
a monolithic sputtering target comprising an Fe-Pt based alloy, Ag, and C, in
15 which the amount of particles generated during sputtering is significantly reduced.
[Selected Drawing] Figure 3